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WIRE GRID POLARIZER AND
MANUFACTURING METHOD THEREOF**(30) **Foreign Application Priority Data**

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(71) Applicant: **SAMSUNG DISPLAY CO., LTD.**,
Yongin-si (KR)**Publication Classification**(72) Inventors: **ATSUSHI TAKAKUWA**, Hwaseong-si
(KR); **Dae Hwan Jang**,
Gwangmyeong-si (KR); **Hyang-Shik
Kong**, Seongnam-si (KR); **Gug Rae Jo**,
Asan-si (KR); **Kyu Young Kim**,
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(2013.01); **G02F 2001/133548** (2013.01)(21) Appl. No.: **15/252,330**(22) Filed: **Aug. 31, 2016****Related U.S. Application Data**(62) Division of application No. 13/470,929, filed on May
14, 2012, now Pat. No. 9,442,236.(57) **ABSTRACT**

A liquid crystal display includes a first substrate. A plurality of fine metal lines is disposed on the first substrate. The plurality of fine metal lines including a plurality of small regions. A second substrate is aligned with the first substrate. A light blocking portion is disposed on the second substrate. The light blocking portion is disposed in a region between the small regions of the plurality of small regions of the plurality of fine metal lines.

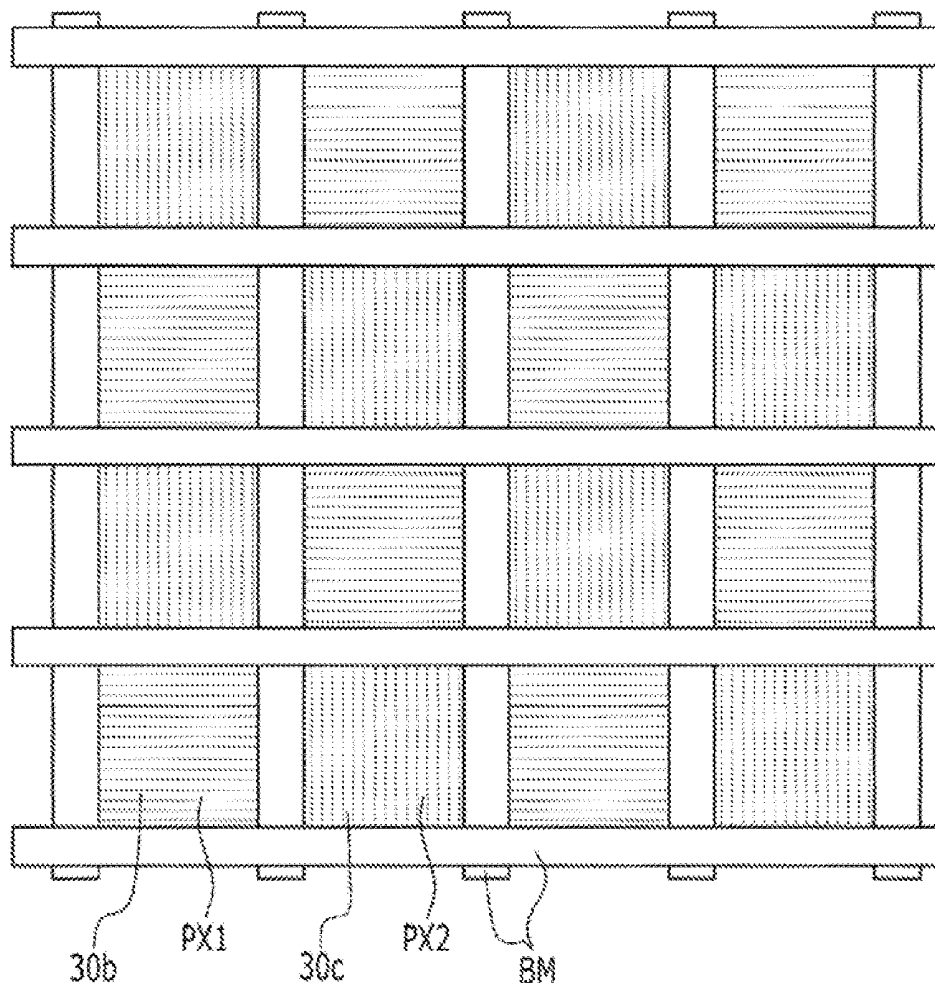


FIG. 1

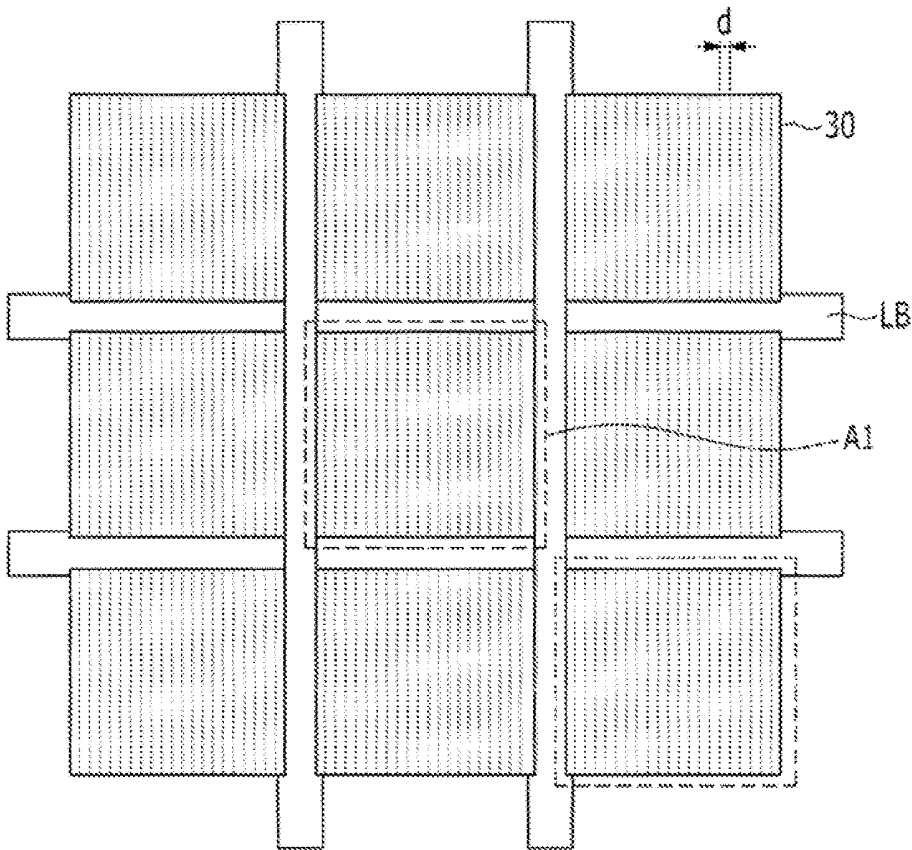


FIG. 2

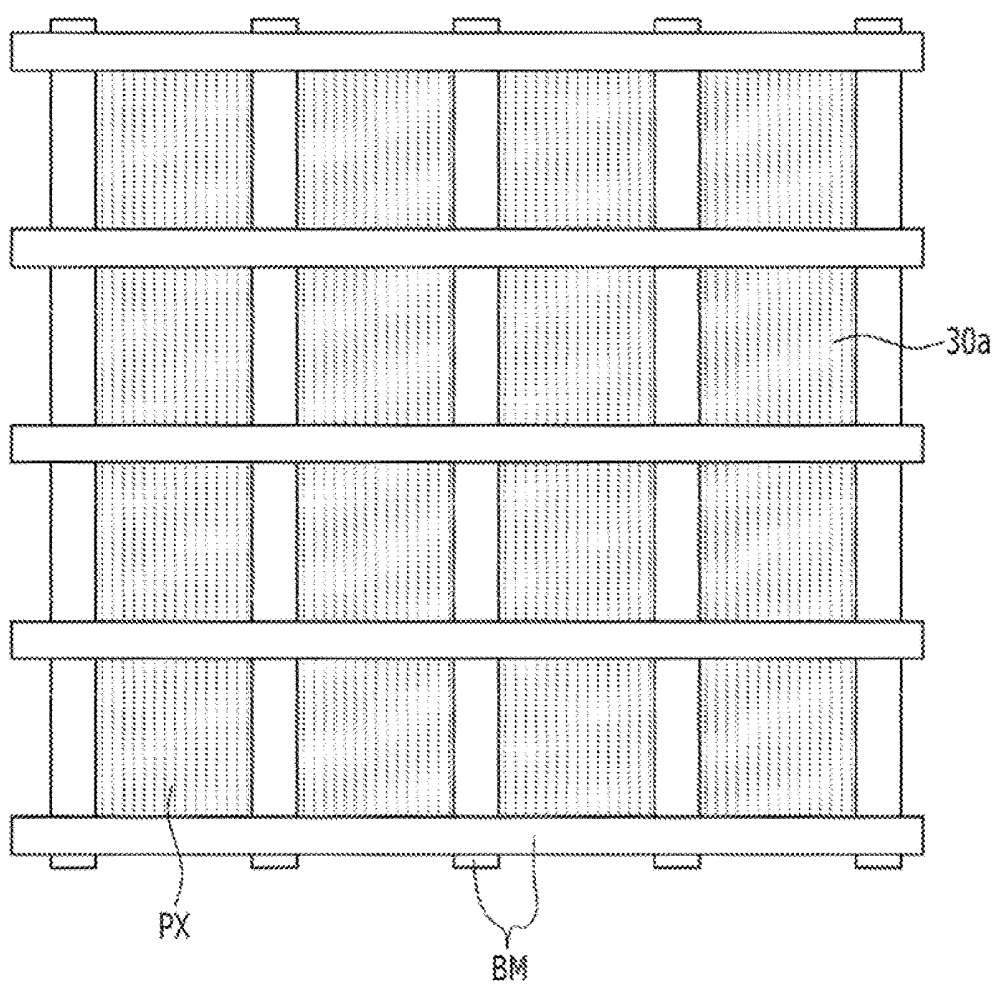


FIG. 3

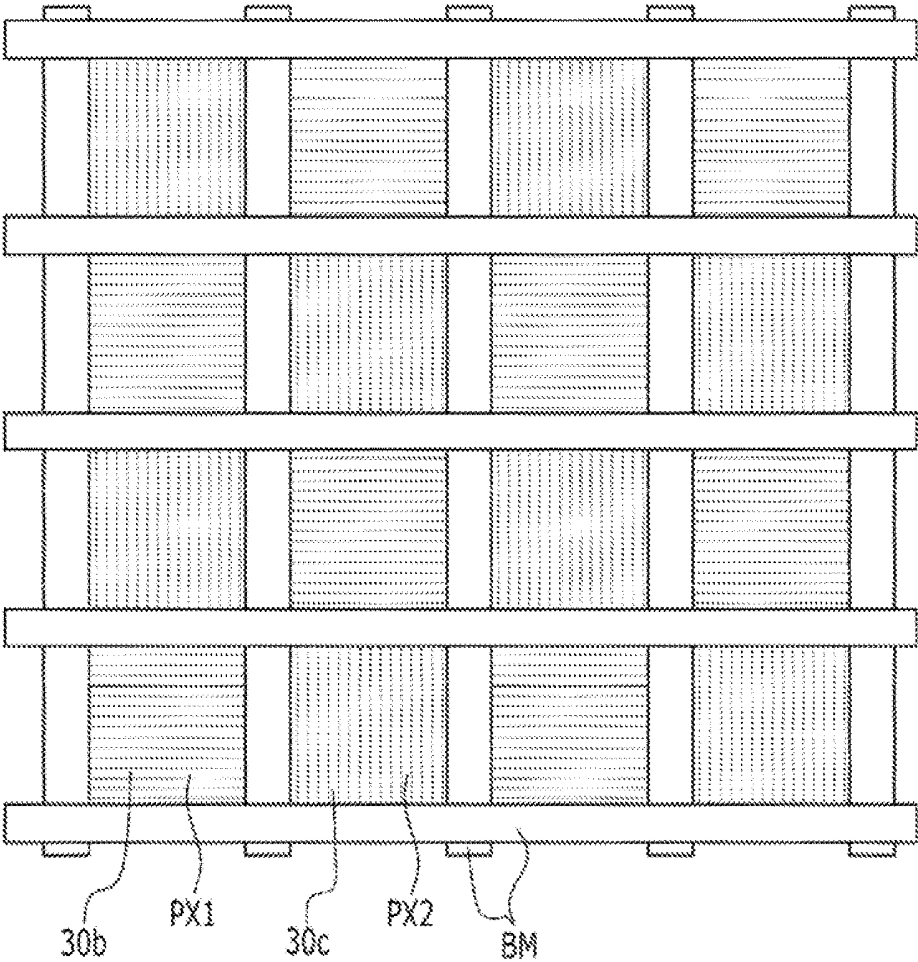


FIG. 4

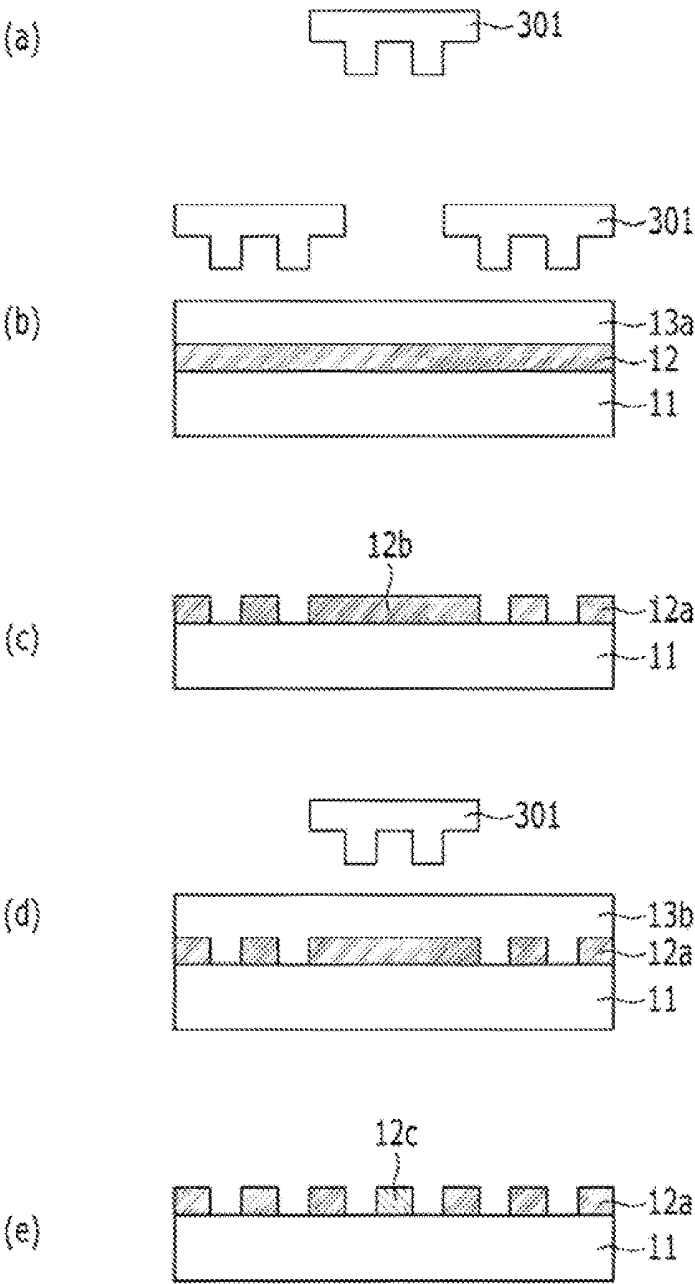


FIG. 5

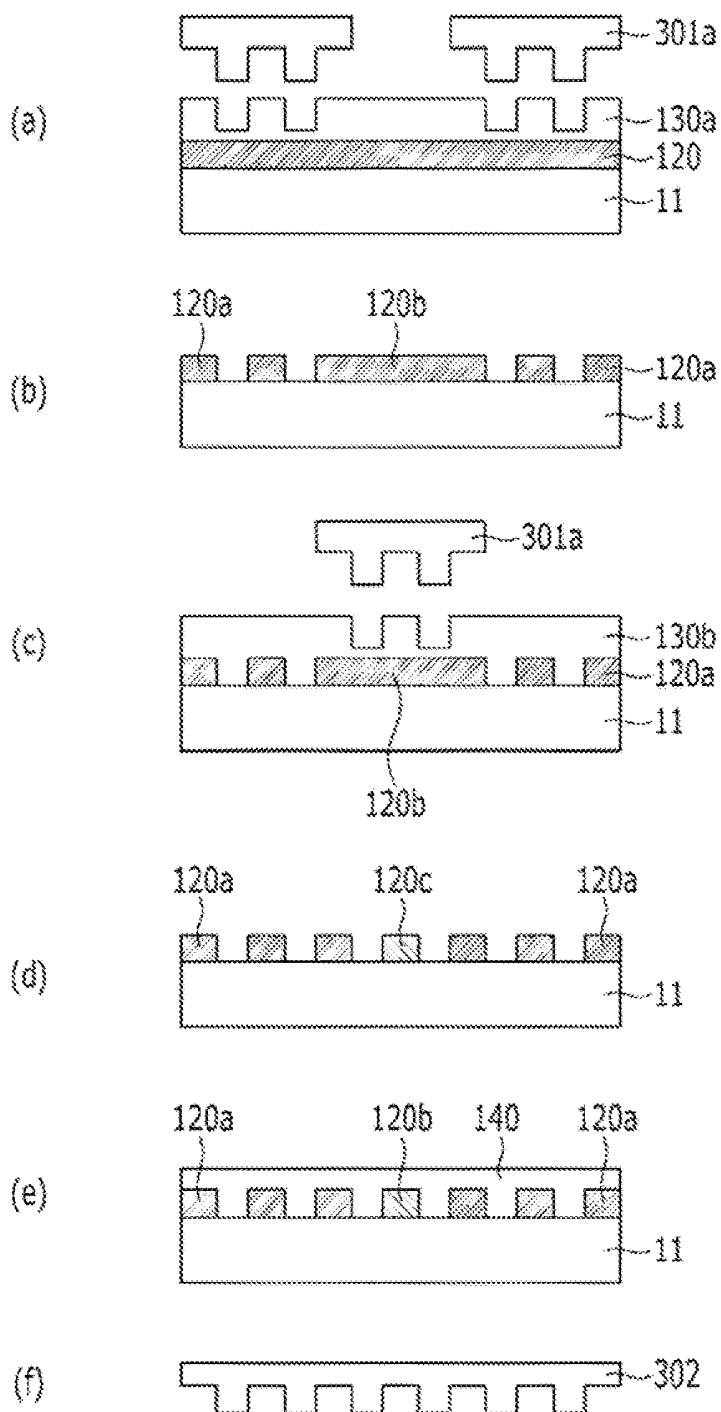


FIG. 6

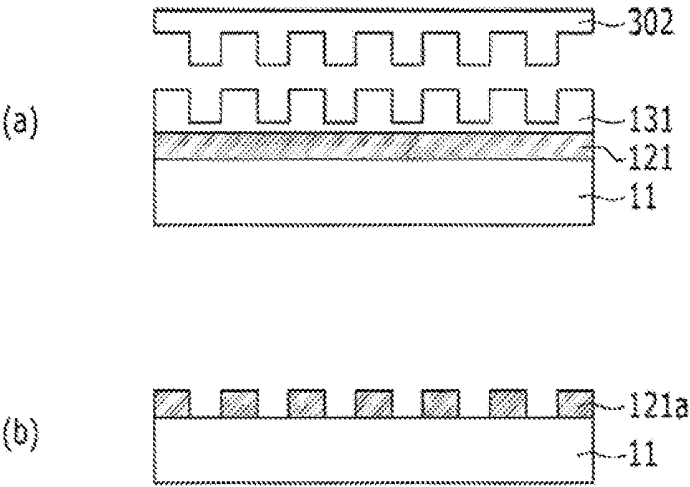
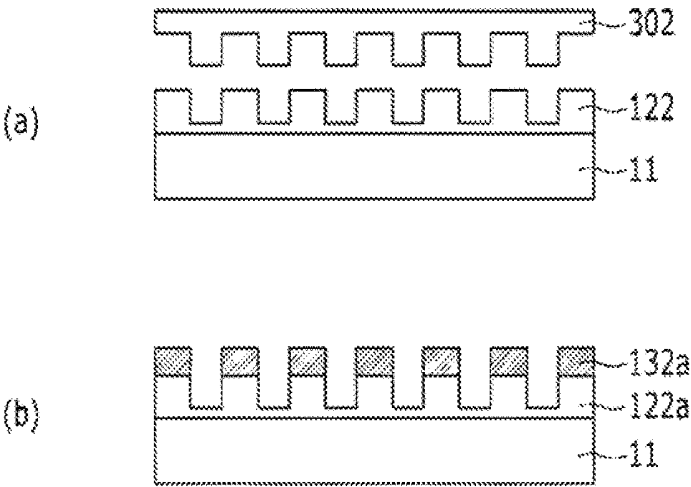


FIG. 7



LIQUID CRYSTAL DISPLAY INCLUDING WIRE GRID POLARIZER AND MANUFACTURING METHOD THEREOF

CROSS-REFERENCE TO RELATED APPLICATION

[0001] This application is a Division of co-pending U.S. patent application Ser. No. 13/470,929, filed on May 14, 2012, which claims priority to and the benefit of Korean Patent Application 10-2011-0118304 filed in the Korean Intellectual Property Office on Nov. 14, 2011, the entire contents of Which are incorporated herein by reference.

TECHNICAL FIELD

[0002] The present invention relates to a liquid crystal display, and more particularly, to a liquid crystal display including a wire grid polarizer and a manufacturing method thereof.

DISCUSSION THE RELATED ART

[0003] The liquid crystal display (LCD) is one of the most common types of flat panel displays currently in production. LCDs may include two panels on which field generating electrodes such as a pixel electrode and a common electrode are formed. A liquid crystal layer is interposed between the two panels. The liquid crystal display generates an electric field on a liquid crystal layer by applying voltage to the field generating electrodes and determines the orientation of liquid crystal molecules of the liquid crystal layer by the generated electric field, thus controlling polarization of incident light so as to display images.

[0004] In general, polarizing plates are attached onto external surfaces of the panels on which the field generating electrodes are formed to control polarization of incident light. Each polarizing plate may be an absorption type polarizing plate which absorbs light that does not have the desired polarization. Therefore, only a small part of a light source supplying light to the liquid crystal display by the polarizing plate is used for displaying an image and as a result, light efficiency of the light source of the liquid crystal display is lowered.

SUMMARY

[0005] Exemplary embodiments of the present invention provide a liquid crystal display including a large area wire grid polarizer without increasing a manufacturing cost and deteriorating a polarization characteristic, and a manufacturing method thereof.

[0006] An exemplary embodiment of the present invention provides a liquid crystal display including a first substrate. A plurality of fine metal lines is disposed on the first substrate and includes a plurality of small regions. A second substrate is aligned with the first substrate. A light blocking portion is disposed on the second substrate, in which the light blocking portion is disposed, in a region between the plurality of small regions of the plurality of fine metal lines.

[0007] In the plurality of small regions, the plurality of fine metal lines may be disposed to have predetermined widths at predetermined intervals in a predetermined direction.

[0008] The widths of the plurality of fine metal lines may be approximately 60 nm or less.

[0009] The intervals the plurality of fine metal lines may be approximately 120 nm or less.

[0010] The entire area of the plurality of fine metal lines may be 200 mm×2.00 mm or more

[0011] A plurality of pixel areas may be disposed on the second substrate and the plurality of small regions may be disposed in the plurality of pixel areas.

[0012] The plurality of pixel areas may include first pixel areas and second pixel areas. In the first pixel area, the plurality of fine metal lines may be uniformly disposed in a first direction. In the second pixel area, the plurality of fine metal lines may be uniformly disposed in a second direction that is different from the first direction.

[0013] The second direction may be perpendicular to the first direction.

[0014] An exemplary embodiment of the present invention provides a method for manufacturing a liquid crystal display including stacking a metal layer on a first substrate. A photosensitive film layer is stacked on the metal layer. A photosensitive film pattern is formed on the photosensitive film layer by a nano-imprint method using a mold. The forming of the photosensitive film pattern may be repeated plural times while moving the mold. A plurality of fine metal patterns including a plurality of small regions corresponding to the molds is formed by etching the metal layer using the photosensitive film pattern. A light blocking portion is formed on a second substrate. The light blocking portion is disposed on boundary portions of the plurality of small regions by aligning the first substrate and the second substrate.

[0015] An exemplary embodiment of the present invention provides a method for manufacturing a liquid crystal display including stacking an etch control layer on a first substrate. A first photosensitive film layer is stacked on the etch control layer. A first photosensitive film pattern is formed on the first photosensitive film layer by a nano-imprint method using a first mold. The forming of the first photosensitive film pattern is repeated plural times while moving the first mold. A plurality of etch control patterns is formed by etching the etch control layer using the first photosensitive film pattern. A first metal layer is stacked on the etch control patterns. A large area second mold including a plurality of first small regions corresponding to the first molds is formed by separating the metal layer from the etch control patterns. A second metal layer is stacked on a second substrate. A second photosensitive film layer is stacked on the second metal layer. A second photosensitive film pattern is formed on the second photosensitive film layer by a nano-imprint method using the second mold. A plurality of fine metal patterns including a plurality of second small regions of the second mold is formed by etching the second metal layer using the second photosensitive film pattern. A light blocking portion is formed on a third substrate. The light blocking portion is disposed at boundary portions of the plurality of second small regions by aligning the second substrate and the third substrate.

[0016] An exemplary embodiment of the present invention provides a method of manufacturing a liquid crystal display including stacking an etch control layer on a first substrate. A first photosensitive film layer is stacked on the etch control layer. A first photosensitive film pattern is formed on the first photosensitive film layer by a nano-imprint method using a first mold. The forming of the first photosensitive film pattern is repeated plural times while

moving the first mold. A plurality of etch control patterns is formed by etching the etch control layer using the first photosensitive film pattern. A first metal layer is stacked on the etch control pattern. A large area second mold including a plurality of first small regions corresponding to the first molds is formed by separating the metal layer from the etch control patterns. A second photosensitive film layer is stacked on a second substrate. A second photosensitive film pattern is formed on the second photosensitive film layer by a nano-imprint method using the second mold. A plurality of fine metal patterns having a plurality of second small regions of the second mold is formed by stacking a metal layer on the second photosensitive film pattern. A light blocking portion is formed on a third substrate. The light blocking portion is disposed on boundary portions of the plurality of second small regions by aligning the second substrate and the third substrate.

[0017] According to exemplary embodiments of the present invention, a large area wire grid polarizer is formed using a small area mold in which a signal line or a light blocking member is disposed at connection portions of the molds or connection portions between the small area wire grid polarizers. Deterioration in a polarization characteristic due to an arrangement difference of the connection portions between the wire grid polarizers may thereby be reduced or prevented. Accordingly, a liquid crystal display including a large area wire grid polarizer may be formed without increasing a manufacturing cost and without deteriorating the polarization characteristic.

BRIEF DESCRIPTION THE DRAWINGS

[0018] A more complete appreciation of the present disclosure and many of the attendant aspects thereof will be readily obtained as the same becomes better understood by reference to the following detailed description when considered in connection with the accompanying drawings, wherein:

[0019] FIG. 1 is a layout view of a liquid crystal display according to an exemplary embodiment of the present invention;

[0020] FIG. 2 is a layout view of a liquid crystal display according to an exemplary embodiment of the present invention;

[0021] FIG. 3 is a layout view of the liquid crystal display according to an exemplary embodiment of the present invention;

[0022] FIG. 4 is a cross-sectional view showing a method of manufacturing the liquid crystal display according to an exemplary embodiment of the present invention;

[0023] FIGS. 5 and 6 are cross-sectional views showing a method of manufacturing the liquid crystal display according to an exemplary embodiment of the present invention; and

[0024] FIG. 7 is a cross-sectional view showing a method of manufacturing the liquid crystal display according to an exemplary embodiment of the present invention.

DETAILED DESCRIPTION OF THE EMBODIMENTS

[0025] Exemplary embodiments of the present invention will be described more fully hereinafter with reference to the accompanying drawings. As those skilled in the art would realize, the described exemplary embodiments may be

modified in various different ways, all without departing from the spirit or scope of the present invention.

[0026] In the drawings, the thickness of layers, films, panels, regions, etc., may be exaggerated for clarity. Like reference numerals may designate like elements throughout the specification. When an element such as a layer, film, region, or substrate is referred to as being "on" another element, it can be directly on the other element or intervening elements may also be present.

[0027] Hereinafter, a liquid crystal display and a manufacturing method thereof according to an exemplary embodiment of the present invention will be described with reference to the accompanying drawings.

[0028] A liquid crystal display according to an exemplary embodiment of the present invention will be described with reference to FIG. 1. FIG. 1 is a layout view of a liquid crystal display according to an exemplary embodiment of the present invention. Referring to FIG. 1, a liquid crystal display according to an exemplary embodiment of the present invention includes a first wire grid polarizer 30 including a plurality of small regions A1. Line widths of fine patterns of the first wire grid polarizer 30 may be approximately 60 nm or less, Distances d between the fine patterns of the first wire grid polarizer 30 may be approximately 120 nm or less. The entire area of the first wire grid polarizer 30 may be approximately 200 mm×200 mm or more.

[0029] A light blocking portion LB is disposed at boundary portions between the small regions A1 of the first wire grid polarizer 30. The light blocking portion LB may be a metal signal line such as a gate line, a data line, and a storage voltage line or a black matrix.

[0030] The first wire grid polarizer 30 may be formed by repeating a step of forming the small region A1.

[0031] As described above, in the liquid crystal display according to an exemplary embodiment of the present invention, the wire grid polarizer 30 having a large area is formed to include the plurality of small regions A1. The light blocking portion LB is disposed at the boundary portions between the small regions A1 of the wire grid polarizer 30 to prevent light from being transmitted. Accordingly, deterioration in a polarization characteristic which may occur at the boundary portions between the small regions A1 of the wire grid polarizer 30 may be reduced or prevented. Therefore, the liquid crystal display including the large area wire grid polarizer may be provided without increasing a manufacturing cost or deteriorating the polarization characteristic.

[0032] A liquid crystal display according to an exemplary embodiment of the present invention will be described with reference to FIG. 2. FIG. 2 is a layout view of a liquid crystal display according to an exemplary embodiment of the present invention.

[0033] Referring to FIG. 2, the liquid crystal display according to an exemplary embodiment of the present invention includes a plurality of pixel areas PX and second wire grid polarizers 30a which are disposed at aperture regions of the pixel areas PX.

[0034] The second wire grid polarizers 30a are formed together on a display panel on which pixel electrodes of the plurality of pixel areas PX of the liquid crystal display are formed, and may be, for example, disposed on the aperture regions of the pixel areas PX through which light from a backlight is transmitted. Line widths of fine patterns of the second wire grid polarizer 30a may be approximately 60 nm or less, Distances between the fine patterns of the second

wire grid polarizer **30a** may be approximately 120 nm or less. The entire area of the first wire grid polarizer **30** may be 200 mm×200 mm or more.

[0035] The second wire grid polarizer **30a** includes a plurality of small regions which are disposed on the aperture regions of the pixel areas PX. Boundary portions between the plurality of small regions are covered by a light blocking member BM. Therefore, since in the boundary portions of the plurality of small regions of the second wire grid polarizer **30a** the light is prevented from being transmitted by the light blocking member BM, deterioration in a polarization characteristic which may occur at the boundary portions of the plurality of small regions of the second wire grid polarizer **30a** may be reduced or prevented. Accordingly, a liquid crystal display including the large area wire grid polarizer may be provided without increasing a manufacturing cost or deteriorating the polarization characteristic.

[0036] A liquid crystal display according to an exemplary embodiment of the present invention will be described with reference to FIG. 3. FIG. 3 is a layout view of the liquid crystal display according to an exemplary embodiment of the present invention.

[0037] Referring to FIG. 3, a liquid crystal display according to an exemplary embodiment of the present invention includes a plurality of first pixel areas PX1 and a plurality of second pixel areas PX2. Third wire grid polarizers **30b** and **30c** are disposed on aperture regions of the first and second pixel areas PX1 and PX2, respectively. The third wire grid polarizers **30b** and **30c** include first polarization portions and second polarization portions, respectively.

[0038] The first polarization portions including fine metal lines arranged in a first direction are disposed in the first pixel areas PX1 and the second polarization portions including fine metal lines arranged in a second direction different from the first direction are disposed in the second pixel areas PX2. The second direction may be perpendicular to the first direction.

[0039] The third wire grid polarizers **30b** and **30c** are formed together on a display panel on which pixel electrodes of the plurality of pixel areas PX of the liquid crystal display are formed. For example, the third wire grid polarizers **30b** and **30c** may be disposed on the aperture regions of the pixel areas PX through which light from a backlight is transmitted. Line widths of fine patterns of the third wire grid polarizers **30b** and **30c** may be approximately 60 nm or less. Distances between the fine patterns of the third wire grid polarizers **30b** and **30c** may be approximately 120 nm or less. The entire area of the first wire grid polarizer **30** may be 200 mm×200 mm or more.

[0040] In the liquid crystal display according to an exemplary embodiment, the first polarization portions **30b** disposed in the first pixel areas PX1 and the second polarization portions **30c** disposed in the second pixel areas PX2 polarize light in directions perpendicular to each other. This structure is used for a liquid crystal display for displaying a 3D image by making polarization directions of a left eye and a right eye different. For example, the first pixel areas PX1 may be pixel areas which are recognized by the left eye and the second pixel areas PX2 may be pixel areas which are recognized by the right eye.

[0041] The third wire grid polarizers **30b** and **30c** include a plurality of small regions disposed on the aperture regions of pixel areas PX. Boundary portions of the plurality of small regions are covered by a light blocking member BM.

Therefore, since in the boundary portions of the plurality of small regions of the third wire grid polarizers **30b** and **30c**, the light is prevented from being transmitted by the light blocking member BM, deterioration in a polarization characteristic which may occur at the boundary portions of the plurality of small regions of the third wire grid polarizers **30b** and **30c** may be minimized or prevented. Accordingly, it is possible to provide the liquid crystal display including the large area wire grid polarizer without increasing a manufacturing cost and deteriorating the polarization characteristic.

[0042] A method of manufacturing the liquid crystal display according to an exemplary embodiment of the present invention will be described with reference to FIG. 4. FIG. 4 is a cross-sectional view showing a method for manufacturing the liquid crystal display according to an exemplary embodiment of the present invention.

[0043] Referring to FIG. 4A, in a method of manufacturing a polarizer of the liquid crystal display according to an exemplary embodiment of the present invention, a small area first mold **301** is manufactured. The mold may be formed of silicon, glass, nickel (Ni), resist, and the like and may be used repeatedly. The mold is formed by a photolithography method so as to have a width and a distance of for example, 50 nm.

[0044] Referring to FIG. 4B, a metal layer **12** is stacked on a substrate **11**, a photosensitive film is stacked on the metal layer **12**, and then a first photosensitive film pattern **13a** is formed from the photosensitive film by a nano-imprint method using a plurality of first molds **301**. A hard mask layer such as silicon oxide (SiO₂) or the like may be stacked between the metal layer **12** and the photosensitive film. When the hard mask layer is provided, it is possible to increase a margin of an etching condition at the time of etching as shown in FIG. 4C. The metal layer **12** may include any one of aluminum (Al), gold (Au), silver (Ag), copper (Cu), chromium (Cr), and iron (Fe). According to an exemplary embodiment, the plurality of first molds **301** are used, but a single first mold **301** may also be used. Further, the first photosensitive film pattern **13a** is formed on a portion of the entire area on which the polarizer is formed and after the mold is moved, the first photosensitive film pattern **13a** is formed again. These steps are repetitively performed and as a result, the first photosensitive film pattern **13a** may be formed in a large area.

[0045] Thereafter, referring to FIG. 4C, after a recess portion of the photosensitive film pattern **13a** is removed, the metal layer **12** is etched using the photosensitive film pattern **13a** as a mask and the remaining photosensitive film pattern is removed by an ashing process, thereby forming a polarizer having a desired fine first metal pattern **12a**. At this time, a second metal pattern **12b** different from the first metal pattern **12a** may be formed on a region between the plurality of first molds **301**. The second metal pattern **12b** may also act as a polarizer.

[0046] The manufactured polarizer is aligned with a manufactured display panel, and thus, the second metal pattern **12b** of the polarizer is aligned with a light blocking portion of the display panel, thereby forming a liquid crystal display.

[0047] In a liquid crystal display according to an exemplary embodiment of the present invention, as shown in FIG. 4D, after the photosensitive film is stacked again on the substrate on which the first metal pattern **12a** and the second

metal pattern **12b** are formed, a second photosensitive film pattern **13b** is formed by nano-imprinting a portion formed with the second metal pattern **12b** using the first molds **301**. After removing a recess portion of the second photosensitive film pattern **13b**, a third metal pattern **12c** is formed by a double nano-imprint method of etching the second metal pattern **12b** using the second photosensitive film pattern **13b** as an etching mask. The third metal pattern **12c** may also cover the boundary portions. The fine metal patterns **12a** and **12c** may be formed on the entire polarizer by the double nano-imprint method. However, even though the double nano-imprint method is used, intervals between the fine metal patterns **12a** and **12c** may not be uniform at boundary portions due to an arrangement error of the mold **301** and the boundary portions may be aligned with the light blocking portion of the display panel.

[0048] As described above, in the liquid crystal display according to an exemplary embodiment of the present invention, the polarizer is formed by repeating the nano-imprint process using the mold having a smaller area than the entire area of the polarizer. The boundary portions between the small regions of the polarizer are aligned with the light blocking portion of the display panel, thereby preventing deterioration in the polarization characteristic which may occur at the boundary portions of the plurality of small regions of the polarizer. Accordingly, a liquid crystal display including a large area wire grid polarizer may be provided without increasing a manufacturing cost or deteriorating the polarization characteristic.

[0049] A method of manufacturing a liquid crystal display according to an exemplary embodiment of the present invention will be described with reference to FIGS. 5 and 6. FIGS. 5 and 6 are cross-sectional views showing a method of manufacturing the liquid crystal display according to an exemplary embodiment of the present invention.

[0050] A method of manufacturing a mold will be described with reference to FIG. 5.

[0051] Referring to FIG. 5A, in a method of manufacturing a polarizer of the liquid crystal display according to an exemplary embodiment of the present invention, a small area first mold **301a** is manufactured. The mold may be formed of silicon, glass, nickel (Ni), resist, and the like and may be used repeatedly. The mold is formed by a photolithography method in order to have a width and a distance of for example, 50 nm.

[0052] After an etch control layer **120** is stacked on a substrate **11** and a photosensitive film is stacked on the etch control layer **120**, a third photosensitive film pattern **130a** is formed by a nano-imprint method using the first mold **301a**.

[0053] Thereafter, referring to FIG. 5B, after removing a recess portion of the photosensitive film pattern **130a**, the etch control layer **120** is etched using the photosensitive film pattern **130a** as a mask and the remaining photosensitive film pattern is removed by an asking process, thereby forming a desired fine first etch control pattern **120a** and a second etch control pattern **120b** disposed at a boundary portion of the first etch control pattern **120a**.

[0054] Referring to FIG. 5C, a fourth photosensitive film pattern **130b** is formed by an additional double nano-imprint method and as shown in FIG. 5D, after removing a recess portion of the fourth photosensitive film pattern **130b**, the second etch control pattern **120b** of the etch control layer **120** is etched again using the fourth photosensitive film pattern **130b** as a mask, thereby forming a third etch control

pattern **120c**. Herein, the steps shown in FIG. 5C and FIG. 5D may be optionally omitted,

[0055] Referring to FIG. 5E, a metal layer **140** is stacked on the substrate **12** including the first etch control pattern **120a** and the third etch control pattern **120c** by electroplating or the like, and then the metal layer **140** is separated, thereby forming a large area second mold **302** as shown in FIG. 5F. Further, the large area second mold **302** is formed as shown in FIG. 5F by the nano-imprint method.

[0056] Next, as shown in FIG. 6A, a second metal layer **121** is stacked on a substrate **11**, a photosensitive film is stacked on the second metal layer **121**, and then a fifth photosensitive film pattern **131** is formed using the large area second mold **302** formed with reference to FIG. 5.

[0057] As shown in FIG. 6B, after removing a recess portion of the fifth photosensitive film pattern **131**, the second metal layer **121** is etched using the fifth photosensitive film pattern **131** as an etching mask, thereby forming a polarizer on which a desired fourth metal pattern **121a** is disposed in a large area.

[0058] Thereafter, a part between small regions corresponding to regions in which the first molds **301a** are disposed when the second mold **302** is formed, is aligned with a light blocking portion of a display panel. Accordingly, deterioration in a polarization characteristic of the polarizer which may occur between the small regions of the polarizer may be reduced or prevented. Accordingly, it is possible to provide the liquid crystal display including the large area wire grid polarizer without increasing a manufacturing cost and deteriorating the polarization characteristic.

[0059] A method for manufacturing a liquid crystal display according to an exemplary embodiment of the present invention will be described with reference to FIG. 5 and FIG. 7.

[0060] First, as described above with reference to FIG. 5, the large area second mold **302** is formed.

[0061] Thereafter, as shown in FIG. 7A, a photosensitive film is stacked on a substrate **11** and a sixth photosensitive film pattern **122** is formed by a nano-imprint method using the second mold **302**. Then, as shown in FIG. 7B, a metal layer is stacked on the sixth photosensitive film pattern **122**, thereby forming a polarizer on which a desired fifth metal pattern **122a** is disposed in a large area.

[0062] Thereafter, a part between small regions corresponding to regions in the first molds **301a** are disposed when the second **302** is formed, is aligned with a light blocking portion of a display panel. Accordingly, it is possible to prevent deterioration in a polarization characteristic of the polarizer which may occur between the small regions of the polarizer. Accordingly, it is possible to provide the liquid crystal display including the large area wire grid polarizer without increasing a manufacturing cost and without deteriorating the polarization characteristic.

[0063] While exemplary embodiments of the present invention have been described in connection with the figures, it is to be understood that the invention is not limited to the disclosed embodiments, but is intended to cover various modifications and equivalent arrangements.

What is claimed is:

1. A method for manufacturing a liquid crystal display, the method comprising:

- stacking a metal layer on a first substrate;
- stacking a photosensitive film layer on the metal layer;

forming a photosensitive film pattern on the photosensitive film layer by a nano-imprint method using a mold; repeating the forming of the photosensitive film pattern multiple times while moving the mold between each repetition;

forming a plurality of fine metal patterns including a plurality of small regions that correspond to the mold by etching the metal layer using the photosensitive film pattern;

forming a light blocking portion on a second substrate; and

disposing the light blocking portion on boundary portions of the plurality of small regions by aligning the first substrate and the second substrate.

2. The method of claim 1, wherein:

in the plurality of small regions, each of the plurality of fine metal lines are disposed to have predetermined width and width in a predetermined direction.

3. The method of claim 2, wherein:

a plurality of pixel areas is disposed on the second substrate and the plurality of small regions is disposed in the plurality of pixel areas.

4. The method of claim 3, wherein:

the plurality of pixel areas include first pixel areas and second pixel areas,

in the first pixel areas, each the plurality of fine metal lines is formed to uniformly extend in a first direction, and

in the second pixel areas, each of the plurality of fine metal lines is formed to uniformly extend in a second direction different from the first direction.

5. The manufacturing method of a liquid crystal display of claim 4, wherein:

the second direction is perpendicular to the first direction.

6. A method for manufacturing a liquid crystal display, comprising:

stacking an etch control layer on a first substrate;

stacking a first photosensitive film layer on the etch control layer;

forming a first photosensitive film pattern on the first photosensitive film layer by a nano-imprint method using a first mold;

repeating the forming of the first photosensitive film pattern multiple times while moving the first mold between repetitions;

forming a plurality of etch control patterns by etching the etch control layer using the first photosensitive film pattern;

stacking a first metal layer on the etch control patterns;

forming a large area second mold including a plurality of first small regions corresponding to the first mold by separating the metal layer from the etch control patterns;

stacking a second metal layer on a second substrate;

stacking a second photosensitive film layer on the second metal layer;

forming a second photosensitive film pattern on the second photosensitive film layer by a nano-imprint method using the second mold;

forming a plurality of fine metal patterns including a plurality of second small regions of the second mold by etching the second metal layer using the second photosensitive film pattern;

forming a light blocking portion on a third substrate; and disposing the light blocking portion at boundary portions of the plurality of second small regions by aligning the second substrate and the third substrate.

7. The method of claim 6, wherein:

in the plurality of second small regions, each of the plurality of fine metal lines are disposed to have predetermined width and interval in a predetermined direction.

8. A method of manufacturing a liquid crystal display, comprising:

stacking an etch control layer on a first substrate;

stacking a first photosensitive film layer on the etch control layer;

forming a first photosensitive film pattern on the first photosensitive film layer by a nano-imprint method using a first mold;

repeating the forming of the first photosensitive film pattern multiple times while moving the first mold between repetitions;

forming a plurality of etch control patterns by etching the etch control layer using the first photosensitive film pattern;

stacking a first metal layer on the etch control pattern;

forming a large area second mold including a plurality of first small regions corresponding to the first mold by separating the metal layer from the etch control patterns;

stacking a second photosensitive film layer on a second substrate;

forming a second photosensitive film pattern on the second photosensitive film layer by as nano-imprint method using the second mold;

forming a plurality of fine metal patterns having a plurality of second small regions of the second mold by stacking a metal layer on the second photosensitive film pattern;

forming a light blocking portion on a third substrate; and disposing the light blocking portion on boundary portions of the plurality of second small regions by aligning the second substrate and the third substrate.

9. The method of claim 8, wherein:

in the plurality of second small regions, each of the plurality of fine metal lines are disposed to have predetermined width and interval in a predetermined direction.

* * * * *

专利名称(译)	包括线栅偏振器的液晶显示器及其制造方法		
公开(公告)号	US20160370651A1	公开(公告)日	2016-12-22
申请号	US15/252330	申请日	2016-08-31
[标]申请(专利权)人(译)	三星显示有限公司		
申请(专利权)人(译)	三星DISPLAY CO. , LTD.		
当前申请(专利权)人(译)	三星DISPLAY CO. , LTD.		
[标]发明人	TAKAKUWA ATSUSHI JANG DAE HWAN KONG HYANG SHIK JO GUG RAE KIM KYU YOUNG		
发明人	TAKAKUWA, ATSUSHI JANG, DAE HWAN KONG, HYANG-SHIK JO, GUG RAE KIM, KYU YOUNG		
IPC分类号	G02F1/1335		
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摘要(译)

液晶显示器包括第一基板。多个细金属线设置在第一基板上。多个细金属线包括多个小区域。第二基板与第一基板对准。遮光部设置在第二基板上。光阻挡部分设置在多个尖齿金属线的多个小区域的小区域之间的区域中。

